

IN THE CLAIMS

Claims 2-3 are pending in this application. Please cancel claim 1 without prejudice or disclaimer, and amend claims 2-3 as follows:

1. (Canceled)
2. (Currently Amended) A method for purifying semiconductor nanoparticles, comprising the steps of:
 - modifying semiconductor nanoparticles with oil-soluble materials for surface modification;
 - converting the oil-soluble materials for surface modification into water-soluble materials for surface modification at the interface between an organic solvent and water;
 - shifting the semiconductor nanoparticles from an organic phase to an aqueous phase by the conversion; and then
 - subjecting the semiconductor nanoparticles, the surfaces of which have been modified with the water-soluble materials for surface modification, to size-selective photoetching, wherein the surface of the semiconductor nanoparticles is dissolved and peeled by the size-selective photoetching, and particle sizes of the semiconductor nanoparticles are regulated and the semiconductor nanoparticles are monodispersed by the dissolution. ~~thereby regulating particle sizes of the semiconductor nanoparticles and monodispersing the semiconductor nanoparticles.~~
3. (Currently Amended) A method for purifying semiconductor nanoparticles, comprising the steps of:
 - modifying semiconductor nanoparticles with oil-soluble materials for surface modification;
 - converting the oil-soluble materials for surface modification into water-soluble materials for surface modification at the interface between an organic solvent and water;
 - shifting the semiconductor nanoparticles from an organic phase to an aqueous phase by the conversion; and then

subjecting the semiconductor nanoparticles, the surfaces of which have been modified with the water-soluble materials for surface modification, to size-selective photoetching, wherein the surface of the semiconductor nanoparticles is dissolved and peeled by the size-selective photoetching, and the materials for surface modification is converted by the dissolution~~whereby the dissolution caused thereby is utilized to peel the surfaces of the semiconductor nanoparticles, thereby converting the materials for surface modification.~~